	Application No.	Applicant(s)	XX
Notice of Allowability	09/845,654	LUKANC ET AL.	
	Examiner	Art Unit	
	Julio J. Maldonado	2822	
	Julio J. Maldonado	2823	
The MAILING DATE of this communication apperall claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in or other appropriate commu IGHTS. This application is so	this application. If not includenication will be mailed in due	ed course. THIS
1. X This communication is responsive to amendment filed on a	10/24/2003		
2. ☑ The allowed claim(s) is/are <u>1-5 and 7-20</u> .	1012412000.		
3. The drawings filed on are accepted by the Examine	r.		
 Acknowledgment is made of a claim for foreign priority ur a) ☐ All b) ☐ Some* c) ☐ None of the: 		r (f).	
 Certified copies of the priority documents have 	been received.		
2. Certified copies of the priority documents have	been received in Application	1 No	
3. Copies of the certified copies of the priority doc	cuments have been received	in this national stage applicat	tion from the
International Bureau (PCT Rule 17.2(a)).			
* Certified copies not received:			
 Acknowledgment is made of a claim for domestic priority ur reference was included in the first sentence of the specifica 	ition or in an Application Data	a Sheet. 37 CFR 1.78.	a specific
(a) The translation of the foreign language provisional a	• •		
 Acknowledgment is made of a claim for domestic priority ur in the first sentence of the specification or in an Application 	Data Sheet. 37 CFR 1.78.		
Applicant has THREE MONTHS FROM THE "MAILING DATE" of below. Failure to timely comply will result in ABANDONMENT of the comply will result in ABANDONMENT of the complex complex compl	this application. THIS THRE	EE-MONTH PERIOD IS NOT	EXTENDABLE
 A SUBSTITUTE OATH OR DECLARATION must be submined in the submined	es reason(s) why the oath or		OTICE OF
 CORRECTED DRAWINGS (as "replacement sheets") mus (a) ☐ including changes required by the Notice of Draftspers 1) ☐ hereto or 2) ☐ to Paper No 		(PTO-948) attached	
(b) ☐ including changes required by the proposed drawing c	orrection filed which	has been approved by the E	xaminer
(c) ☐ including changes required by the attached Examiner's			
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t			back) of
9. DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT FOR T	sit of BIOLOGICAL MATE THE DEPOSIT OF BIOLOGIC	RIAL must be submitted. P CAL MATERIAL.	Note the
Attachment(s)			
1⊠ Notice of References Cited (PTO-892)	5☐ Notice of Info	rmal Patent Application (PTO	-152)
 Notice of Draftperson's Patent Drawing Review (PTO-948) Information Disclosure Statements (PTO-1449 or PTO/SB/08) Paper No 		nmary (PTO-413), Paper No.	·
	3), 7⊠ Examiner's A	mendment/Comment	
4 Examiner's Comment Regarding Requirement for Deposit of Biological Material	8∏ Examiner's Si 9∏ Other .	tatement of Reasons for Allov	vance
	J J		

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DETAILED ACTION

1. The cancellation of claim 6 is acknowledged.

- 2. The rejection of claims 1-5 and 7-20 in action mailed on 09/25/2003 is withdrawn in view of applicants' amendments.
- 3. Claims 2-5 and 7-20 are pending in the application.

Allowable Subject Matter

- 4. Claims 2-5 and 7-20 are allowed.
- 5. The following is an examiner's statement of reasons for allowance:

The prior art of record, Tang et al. to U.S. 6,156,485 teach in Figs.4A-4D and related text a method of high aspect ratio etching including depositing a reflective metal layer (230) over a gate material layer (220), wherein said reflective metal layer (230) comprises tungsten; depositing a mask layer (150, 230) over the reflective metal layer (230), wherein said mask layer (150, 230) comprises a layer of anti-reflective coating (ARC) (230) and a layer of resist (150); removing portions of the anti-reflective coating (230) to form a pattern; etching the reflective metal layer (230) using the pattern formed from the removed portions of the anti-reflective coating (230); removing the anti-reflective coating (230); and removing portions of the gate material layer (220) using the pattern from the removed portions of the anti-reflective coating (230) transferred to the metal layer (230), wherein said ARC layer (230) comprises silicon oxynitride (SiON) and wherein the reflective metal layer is used as a hardmask (column 7, line 16 – column 8, line 3).

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Tang et al. fail to teach depositing a polysilicon layer; and trim etching the tungsten layer, wherein the antireflective coating is removed during said trim etch.

Maa to U.S. 4,460,435 teaches in Figs.1-4 and related text a patterning process including depositing a polysilicon layer (16) over an oxide layer (14) overlying a substrate (10); depositing a metal layer (18) over the polysilicon layer (16), wherein said metal comprises tungsten; depositing a photoresist layer (20) over the metal layer (18); patterning the photoresist layer (20); and trim etching the metal layer (18), wherein the etching step comprises isotropic etching (column 3, lines 11 – 59).

However, Maa fails to teach depositing an antireflective coating over the metal layer.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

6. Papers related to this application may be submitted directly to Art Unit 2823 by facsimile transmission. Papers should be faxed to Art Unit 2823 via the Art Unit 2823 Fax Center located in Crystal Plaza 4, room 3C23. The faxing of such papers must conform to the notice published in the Official Gazette, 1096 OG 30 (15 November 1989). The Art Unit 2823 Fax Center number is (703) 305-

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3432. The Art Unit 2823 Fax Center is to be used only for papers related to Art Unit 2823 applications.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to **Julio J. Maldonado** at **(703) 306-0098** and between the hours of 8:00 AM to 4:00 PM (Eastern Standard Time) Monday through Friday or by e-mail via julio.maldonado@uspto.gov. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Olik Chaudhuri, can be reached on **(703) 306-2794**.

Any inquiry of a general nature or relating to the status of this application should be directed to the **Group 2800 Receptionist** at **(703) 308-0956**.

JMR 1/8/04

Primary Examiner